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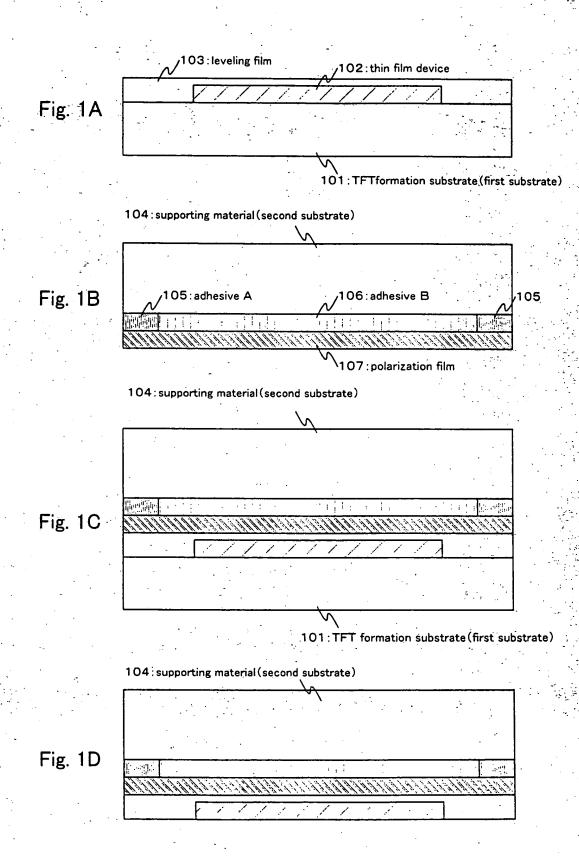
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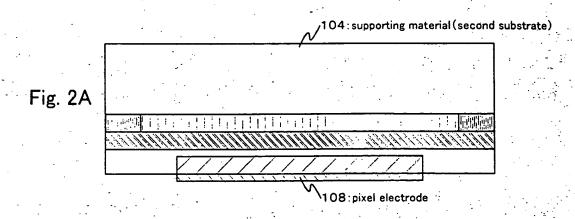
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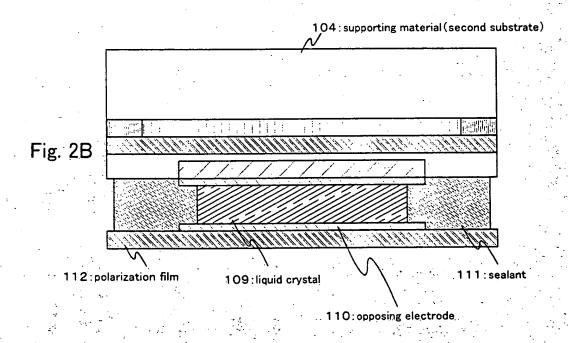
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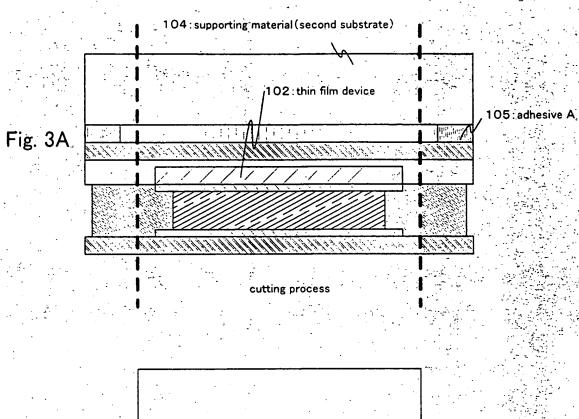
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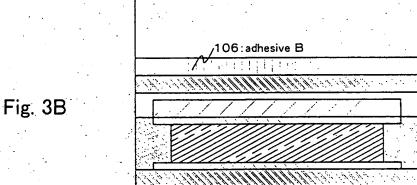


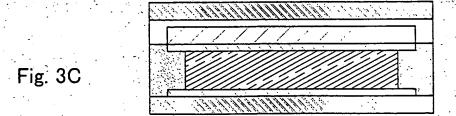


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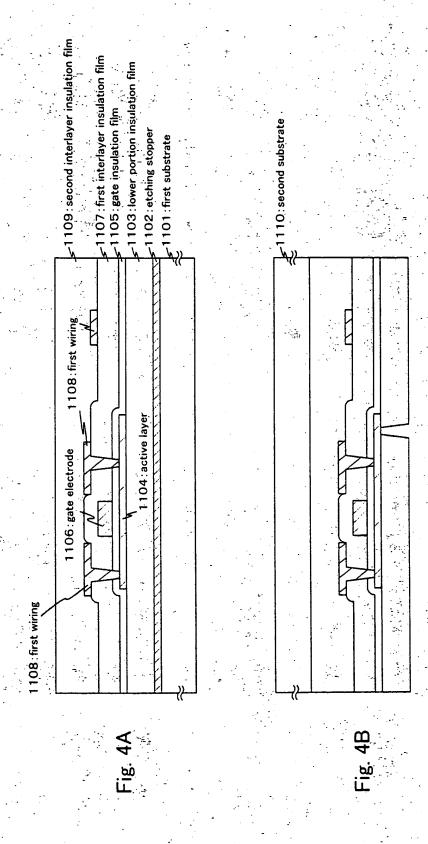






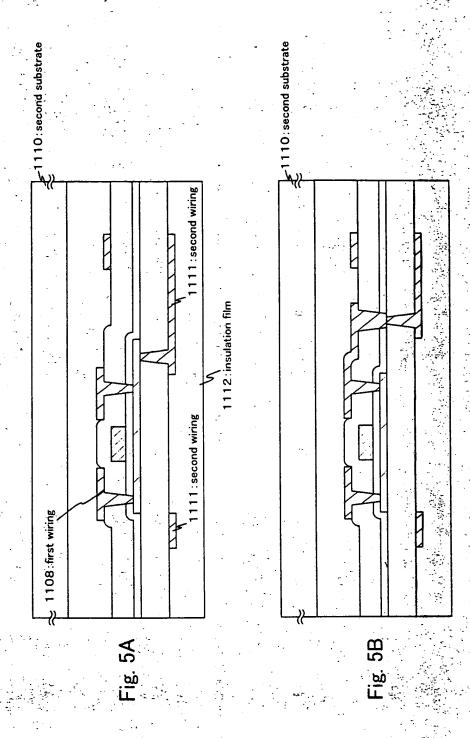
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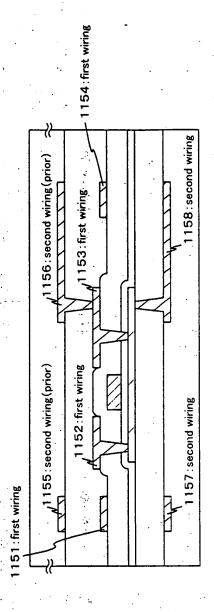
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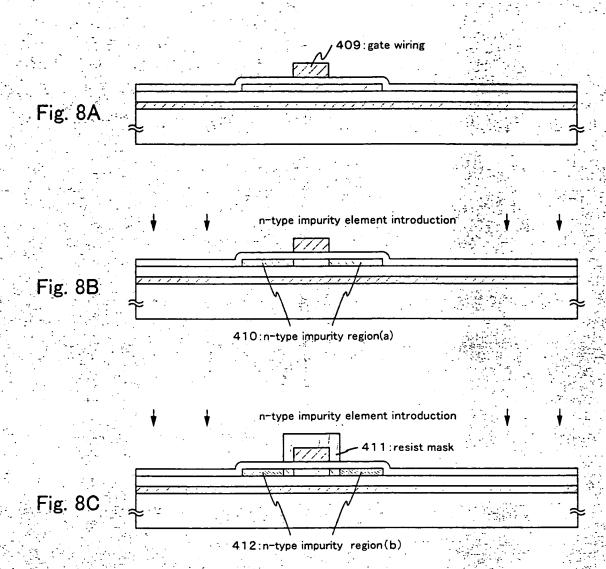
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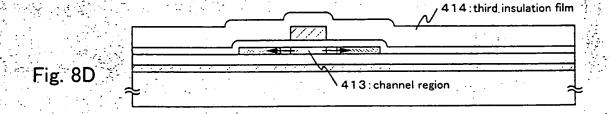
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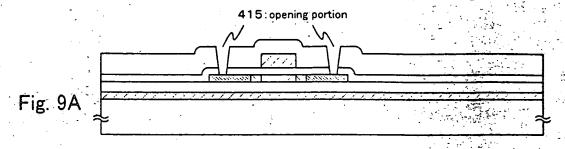
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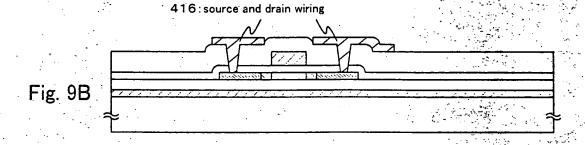


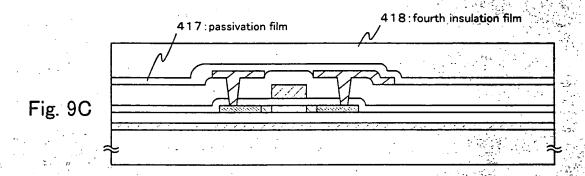


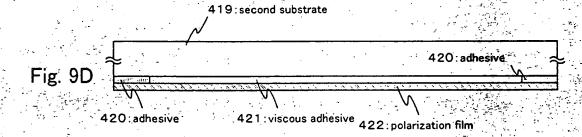
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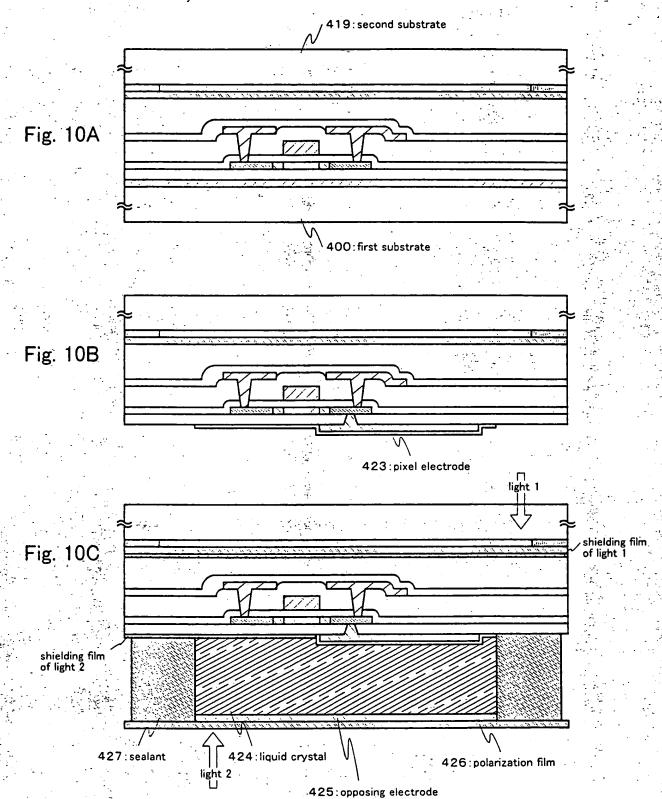




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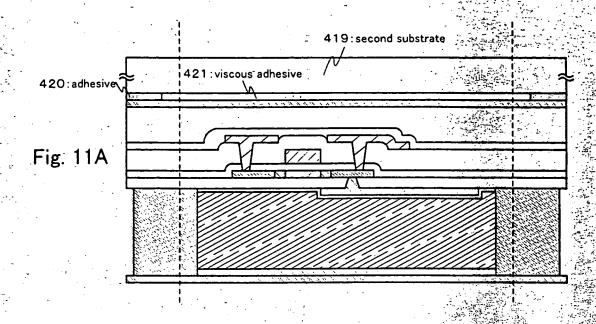
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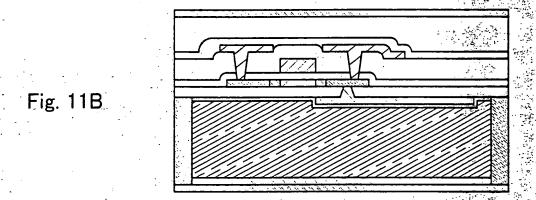
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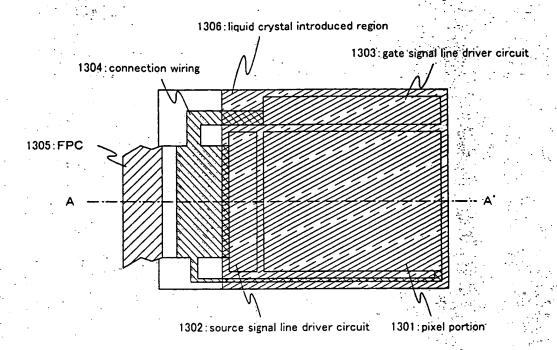


Fig. 12

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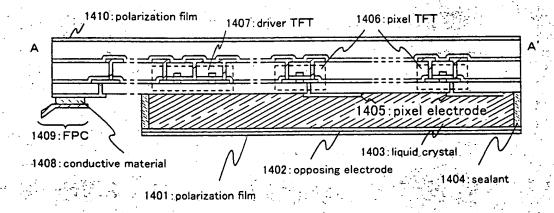
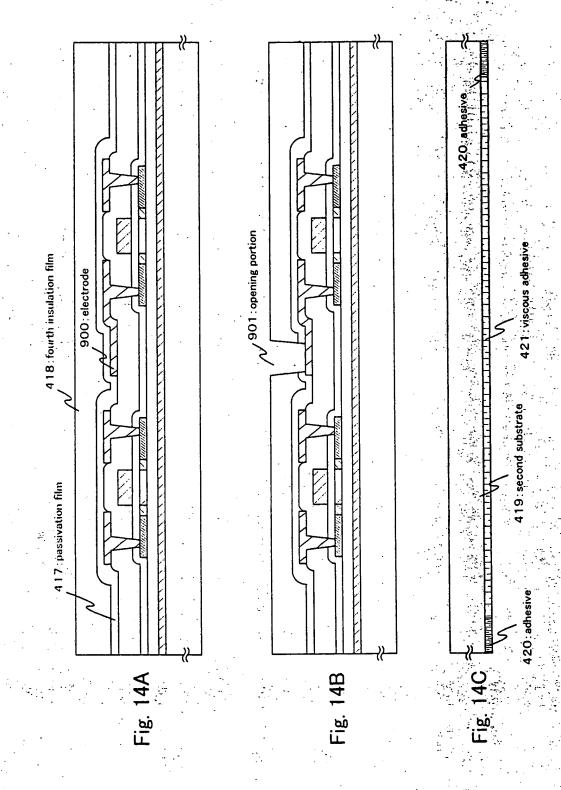


Fig. 13

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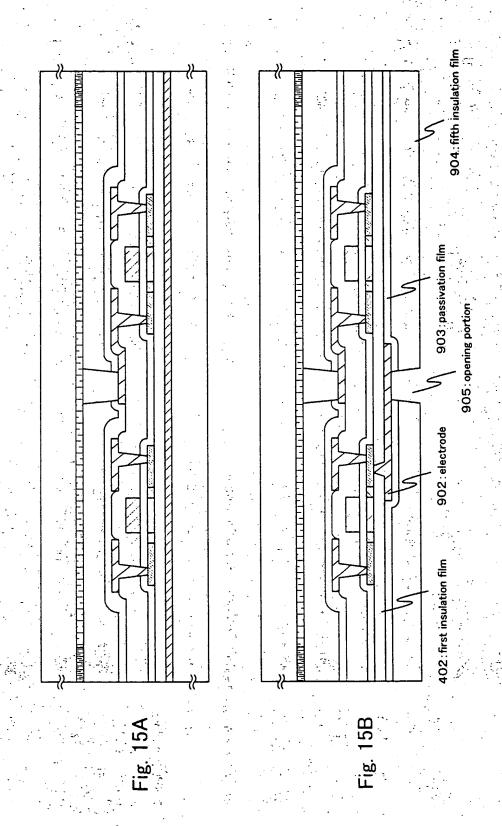
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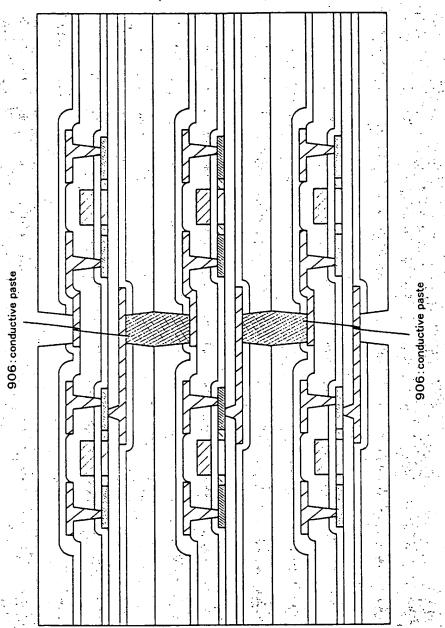
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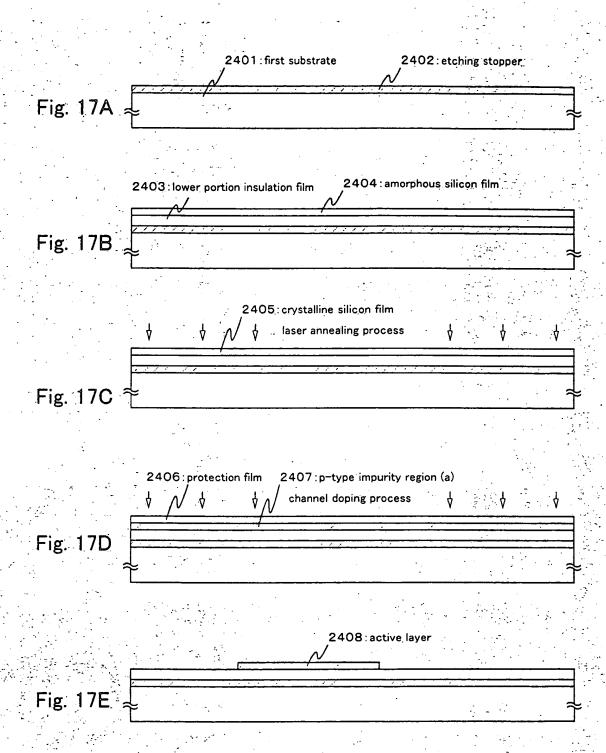
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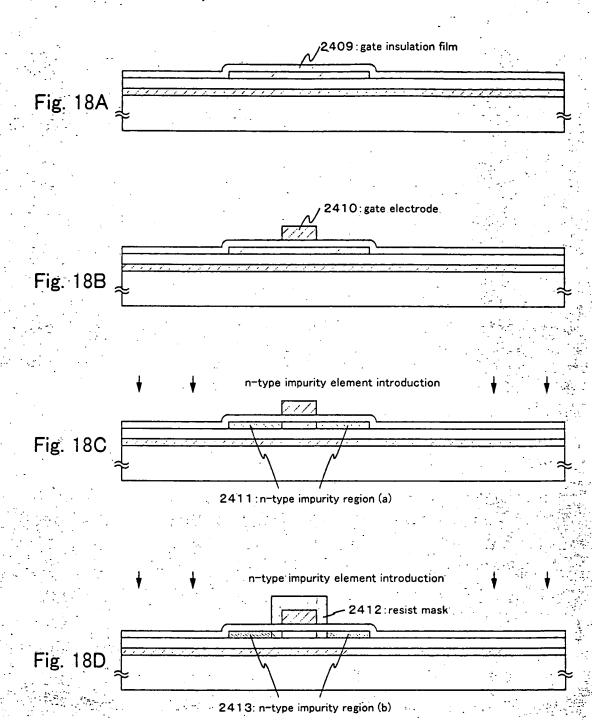
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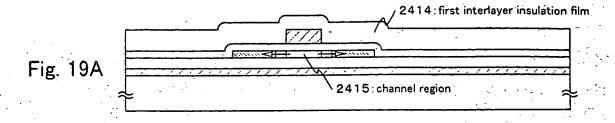
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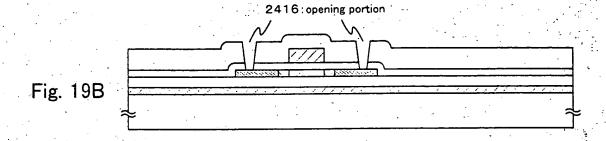
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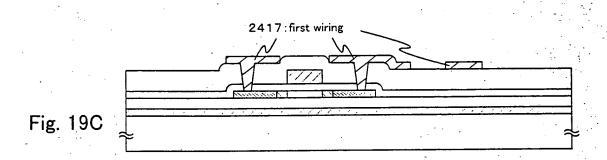


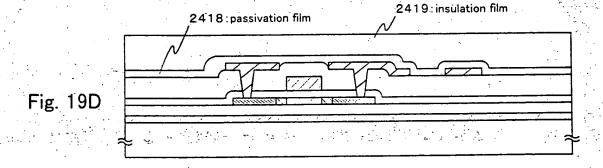
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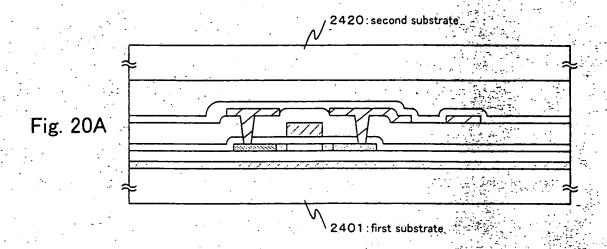


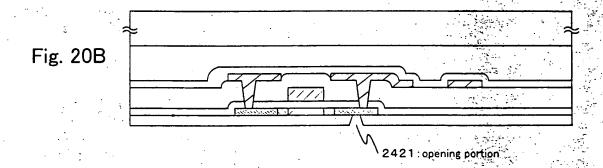


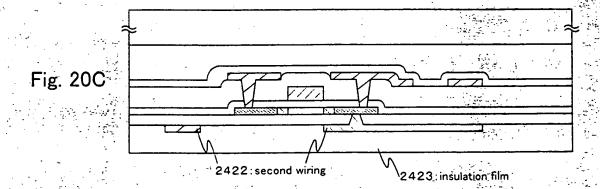


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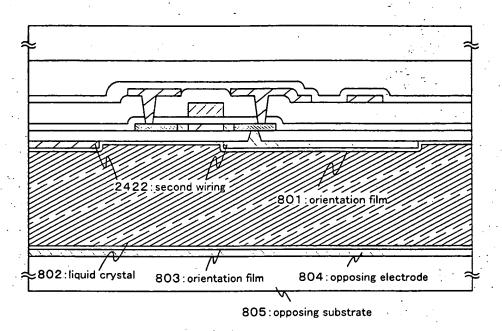


Fig. 21

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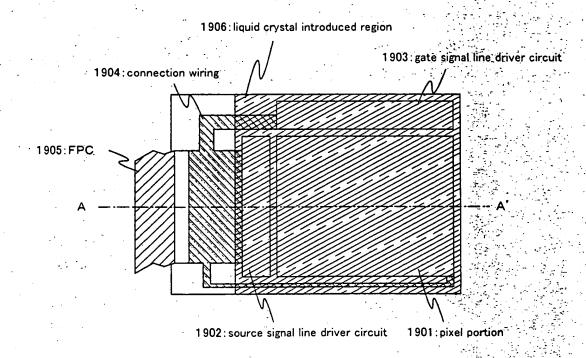


Fig. 22

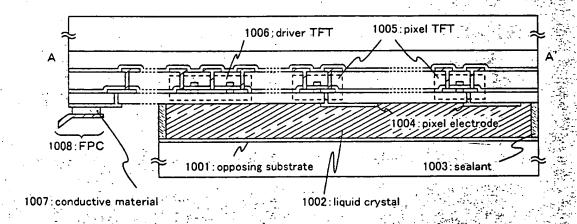
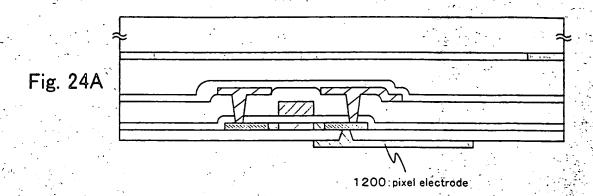


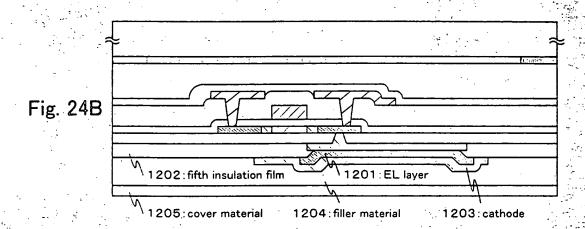
Fig. 23

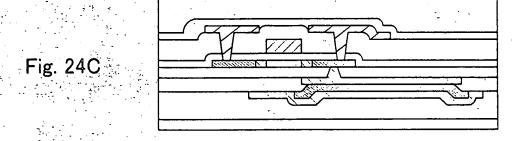
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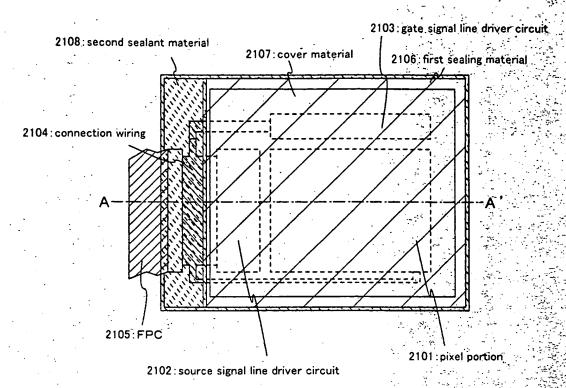


Fig. 25

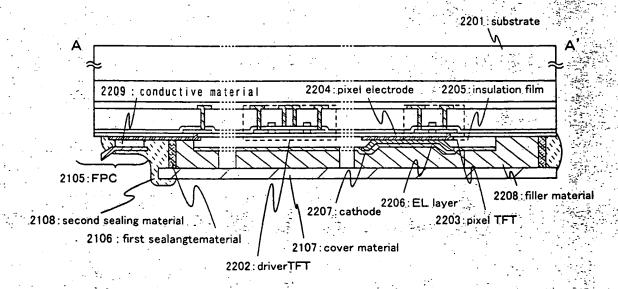


Fig. 26

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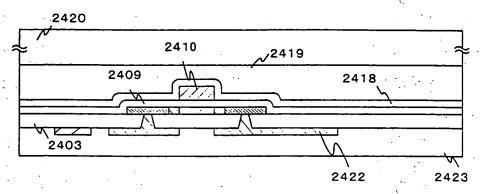


Fig. 27

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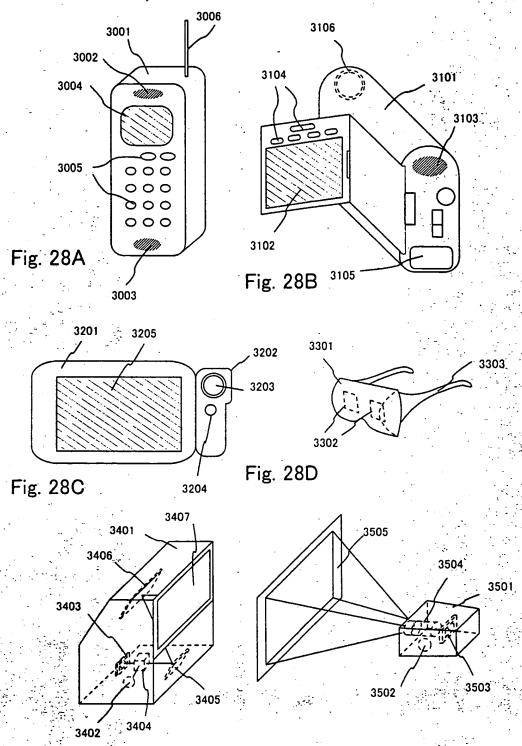


Fig. 28E

Fig. 28F